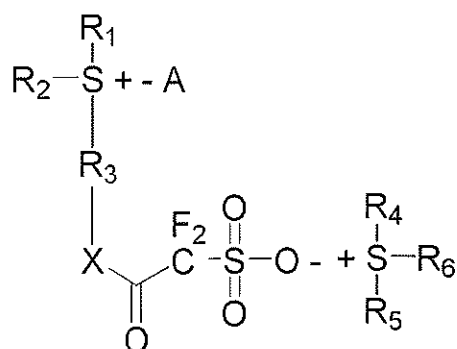


SULFONIUM COMPOUND, PHOTOACID GENERATOR, AND RESIST COMPOSITION

ABSTRACT OF THE DISCLOSURE

A sulfonium compound represented by the following formula (1), a photoacid generator containing the sulfonium compound, and a resist composition containing the photoacid generator are provided:

[Chemical Formula 1]



wherein X represents an electron donor group; R₁ and R₂ each independently represent an alkyl group or the like; R₄ to R₆ each independently represent an alkyl group, or the like; R₃ represents a cyclic alkenediyl group or the like; and -A represents an anion. The sulfonium compound has a photon yield that is controllable by introducing different absorbers to the cation region in one molecule, can address the inconvenience of using a mixture of different photoacid generators when the sulfonium compound is applied as a photoacid generator, has excellent miscibility in a resist, and has enhanced resolution and line edge roughness.

Figure 1